

IV. Plenary Speakers

● Plenary Session 1

Prof. Hao-Chung Kuo

(Nat'l Yang Ming Chiao Tung Univ., Taiwan)



Date & Time	October 14 (Mon.) / 09:20-10:00
Location	Room A (Monterosso, B1F)
Session Chair	Prof. In-Hwan Lee (Korea Univ., Korea)
Title	GaN Micro-LED Array for Chip-to-Chip Interconnection

Biography

Education

Ph.D., UNIVERSITY OF ILLINOIS AT CHAMPAIGN-URBANA
 Department of Electrical and Computer Engineering, Dec. 1998, GPA: 4.0/4.0
 M.S., RUTGERS UNIVERSITY AT NEW BRUNSWICK
 Department of Electrical Engineering (Electronics), May 1995, GPA:4.0/4.0
 B.S., NATIONAL TAIWAN UNIVERSITY, TAIPEI
 Department of Physics, May 1990, GPA: 3.5/4.0

Experience

05/2021- now, Director(所長), Semiconductor Research Center, Hon Hai Research Institute.
 08/2013- now, Distinguished Professor, National Chiao-Tung University, Hsin-Tsu, Taiwan
 (終身特聘教授)
 08/2013- 08/2016, Associate Vice President, office of International Affair; NCTU
 08/2009-01/2010 Chairman & Director(所長), Institute of Electro-optical Engineering, National Chiao-Tung University,
 08/2007-08/2012 Professor, National Chiao-Tung University, Hsin-Tsu, Taiwan
 08/2010-08/2012 TSMC technical director for GaN on Si SiC LED and HEMT (on leave from University)

經歷

國立陽明交通大學光電工程學系 講座教授
 台積固態照明股份有限公司 處長
 美國華星光通科技股份有限公司雷射 部門經理
 美國安捷倫科技光纖通訊部門 研發工程師
 美國貝爾實驗室異質界面半導體部 研究助理

● Plenary Session 2

Prof. Jun Suda

(Nagoya Univ., Japan)



Date & Time	October 14 (Mon.) / 10:00-10:40
Location	Room A (Monterosso, B1F)
Session Chair	Prof. In-Hwan Lee (Korea Univ., Korea)
Title	Vertical GaN Power Devices on GaN Substrates

Biography

Dr. Jun Suda is a Professor of Electronics at Nagoya University from 2017. He was born in 1969 in Japan. He received the B.E. (1992), M.E. (1994) and Ph. D. (1997) degrees from Kyoto University. From 1992 to 1997, he worked on molecular-beam epitaxy (MBE) and structural and optical characterization of ZnMgSSe strained quantum well structures for short-wavelength optoelectronics. In 1997, he began research on group-III nitride semiconductors (III-N) and SiC as a Research Associate at Kyoto University. His research interests include optical/electrical/structural characterization of III-N and SiC materials, heteroepitaxial growth of III-N by MBE, functional integration of III-N and SiC materials, design and fabrication of SiC and GaN-based power devices as well as high-frequency devices. He is a Director of Transformative Energy Electronics Facilities (C-TEFs) at Nagoya University, which is a semiconductor clean room designed for nitride semiconductors. He has authored or co-authored over 250 publications in peer-reviewed journals and international conferences, Dr. Suda is a Fellow of the Japan Society of Applied Physics.

● Plenary Session 3

Prof. Bo Shen

(Peking Univ., China)



Date & Time	October 15 (Tue.) / 09:00-09:40
Location	Room A (Monterosso, B1F)
Session Chair	Prof. Young Joon Hong (Sungkyunkwan Univ., Korea)
Title	Recent Progress on the Large Lattice Mis-Matched Epitaxial Growth and Defect Control of III-Nitride Semiconductors

Biography

Prof. Bo SHEN, the Cheung Kong Professor in Peking University, China, was born in 1963. He received his Ph.D in Tohoku University in Japan in 1995, and took his postdoctoral research in the University of Tokyo between 1998-2000. He obtained the Outstanding Youth Foundation of NSF of China in 2003. His main research field is III-nitride wide band-gap semiconductor physics, materials and devices. He used to be the chief scientist of the National 973 program and the leader of the overall expert group of the National 863 program "The Third Generation Semiconductor" in China. So far, he has published more than 400 contributed papers, compiled 4 Chinese/English academic monographs, and owned more than 80 invention patents in this field.

● Plenary Session 4

Prof. Debdeep Jena

(Cornell Univ., USA)



Date & Time	October 17 (Thu.) / 10:50-11:30
Location	Room A (Monterosso, B1F)
Session Chair	Prof. Wan Sik Hwang (Korea Aerospace Univ., Korea)
Title	Ultrawide Bandgap Semiconductors for Power Electronics: Aluminum Nitride, Gallium Oxide, Diamond

Biography

Debdeep Jena is the David E. Burr Professor of Engineering at Cornell University. His teaching and research are in the quantum physics of semiconductors and electronic and photonic devices based on quantized semiconductor structures (e.g. Nitrides, Oxides, 2D Materials), and their heterostructures with superconductors, ferroelectrics and magnets, with device applications in energy-efficient transistors, light-emitting diodes and RF and power electronics and quantum computation and communications.

The research from his group has been published in more than 300 journal papers including in Science, Nature, Physical Review Letters, Applied Physics Letters and Electron Device Letters and garnered several patents. He is a fellow of the American Physical Society and is the winner of teaching awards and research awards such as the ISCS young scientist award in 2012, MBE young scientist award in 2014, the IBM faculty award in 2012, and the Intel Outstanding Research award in 2020. He is the author of the new textbook "Quantum Physics of Semiconductor Materials and Devices"

● Plenary Session 5

CTO Samuel Cho

(RFHIC, Korea)



Date & Time	October 17 (Thu.) / 11:30-12:10
Location	Room A (Monterosso, B1F)
Session Chair	Prof. Wan Sik Hwang (Korea Aerospace Univ., Korea)
Title	GaN Device-Based Radio Frequency and Microwave Technology

Biography

Dr. Samuel Cho is the co-founder and chief technology officer of RFHIC Corporation, responsible for leading RFHIC's R&D department for wireless infrastructure, defense & aerospace, and RF energy applications.

Founded Radio Frequency Hybrid Integrated Circuits (RFHIC) in August 1999, starting with an incurable need for cost-effective GaAs components for satellite applications within South Korea. As Co-Founder and CTO he led RFHIC's pioneering movement towards gallium nitride (GaN) on silicon carbide (SiC) technology for commercial telecommunication, defense & aerospace, and ISM applications.

Cho has over 40 years of RF & Microwave expertise in gallium nitride (GaN) technology. As Co-founder and Chief Technology Officer of RFHIC, Dr. Cho focuses on pioneering breakthrough semiconductor technology for next-generation commercial RF & Microwave applications.

He holds a bachelor's degree in electrical engineering from Kwangwoon University, a master's degree, and Ph.D degree in electrical engineering from Yonsei University.

● Oral Sessions

[MA1] Symposium GL: III-N Materials and Lighting Devices (1/7)

Session Date	Oct. 14(Mon.), 2024
Session Time	11:00-12:25
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Young Joon Hong (Sungkyunkwan University, Korea) Prof. Bin Liu (Nanjing University, China)

[MA1-1] *Keynote

11:00-11:35

High-Power InGaN-Based Red Micro-LEDs and Their Potential to Lasers

Kazuhiro Ohkawa and Daisuke Iida

King Abdullah University of Science and Technology (KAUST), Saudi Arabia

[MA1-2] *Invited

11:35-12:00

Ultrasmall Blue, Green, and Red InGaN Micro-LEDs

Lai Wang, Luming Yu, Zhibiao Hao, and Yi Luo

Tsinghua University, China

[MA1-3] *Invited

12:00-12:25

Latest Advances in Green and Red InGaN LEDs

Hee Jin Kim

Lumileds LLC, USA



[MB1] Symposium GE: III-N Materials and Electronic Devices (1/7)

Session Date	Oct. 14(Mon.), 2024
Session Time	11:00-12:30
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Prof. Manabu Arai (Nagoya University, Japan) Prof. Ho-Young Cha (Hongik University, Korea)

[MB1-1] *Keynote

11:00-11:35

Controlling Interface States in GaN Power Transistors

Tamotsu Hashizume

Nagoya University, Japan

[MB1-2] *Invited

11:35-12:00

Gate Dielectric Deposition for GaN-Based MIS Devices Using Mist-CVD

Zenji Yatabe¹, Hadirah Radzuan¹, Masaya Fukumitsu¹, Keigo Bito¹, Ryota Ochi², Yusui Nakamura¹, and Taketomo Sato²

¹*Kumamoto University, Japan*, ²*Hokkaido University, Japan*

[MB1-3]

12:00-12:15

Low Noise and High Linearity Millimeter-Wave GaN-Based MIS-HEMTs Fabricated with MOCVD-SiNx as Gate Insulator

Jing Yuan^{1,2}, Xiaojuan Chen^{1,2}, Ke Wei^{1,2}, Guanjun Jing^{1,2}, Jianchao Wang^{1,2}, Liu Wang^{1,2}, Yichuan Zhang¹, Yankui Li¹, Yixu Yao¹, and Sen Huang^{1,2}

¹*Institute of Microelectronics of Chinese Academy of Sciences, China*, ²*University of Chinese Academy of Sciences, China*

[MB1-4]

12:15-12:30

Demonstration of AlGaIn/GaN Planar Channel-Fully-Controlled MIS-HEMT on Si Substrate for Low-Voltage RF Applications

Xinkun Zhang^{1,2}, Quan Dai², Yu Zhou^{1,2}, Qian Li^{1,2}, Xiaoning Zhan^{1,2}, Haoran Qie², Jianxun Liu^{1,2}, Qian Sun^{1,2}, and Hui Yang^{1,2}

¹*University of Science and Technology of China, China*, ²*Suzhou Institute of Nano-Tech and Nano-Bionics, Chinese Academy of Sciences, China*

[MC1] Symposium SiC: SiC Materials and Devices (1/4)

Session Date	Oct. 14(Mon.), 2024
Session Time	11:00-12:25
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Prof. Noboru Ohtani (Kwansei Gakuin University, Japan) Dr. Seong-Min Jeong (KICET, Korea)

[MC1-1] *Keynote**11:00-11:35****Review of Resonac SiC Epitaxial Wafers for Power Devices**

H. Kanazawa

*Resonac Corporation, Japan***[MC1-2] *Invited****11:35-12:00****Recent Research Progress in 200 mm SiC Substrate and Epi Material**

Chunjun Liu, Yanfang Lou, Yu Guo, and Jian Yang

*TanKeBlue Semiconductor Co., Ltd., China***[MC1-3] *Invited****12:00-12:25****Silicon Carbide Innovation and Insights from 200mm Pilot Line at IME, Singapore**

N. Singh, U. Chand, S. Kumar, X. S. Nguyen, A.Y. Hannan, V.Q.G. Roth, Y.-C. Chien, P. Vudumula, G. Tang, A. Ranjan, A. Sundaram, L. K. Bera, and S. Chung

*Institute of Microelectronics, Agency for Science, Technology, and Research (A*STAR), Singapore*



[MA2] Symposium GL: III-N Materials and Lighting Devices (2/7)

Session Date	Oct. 14(Mon.), 2024
Session Time	13:45-15:40
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Dong-Seon Lee (GIST, Korea) Prof. Yong-Ho Ra (Jeonbuk National University, Korea)

[MA2-1] *Invited

13:45-14:10

Characterizing and Understanding the Performance of Micro-Sized Light-Emitting Diodes

Dong-Soo Shin¹, Hyundon Jung², and Jong-In Shim¹

¹Hanyang University, Korea, ²EtaMax Co., Ltd., Korea

[MA2-2]

14:10-14:25

Thermal Influence on the Electro-Optical Characteristics of the InGaN-Based Blue & Green Micro-Light-Emitting Diode

Shyam Mohan, Joocheol Jeong, Jooyong Park, Joonhyuk Lee, Jaejin Heo, and Okhyun Nam

Tech University of Korea, Korea

[MA2-3]

14:25-14:40

Studies of Deep State Defects Introduced by RIE in the Sidewalls of GaN/InGaN Nano and MicroLEDs and the Effects of Different Treatments in Mitigating the Adverse Impact of Such Defects

Alexander Y. Polyakov¹, In-Hwan Lee², Yeong-Hoon Cho², Luiza A. Alexanyan¹, Mikhail L. Skorikov³, Anton A. Vasilev¹, Andrei A. Romanov¹, Nikolai R. Matros¹, Anastasiia I. Kochkova², and Stephen J. Pearton⁴

¹National University of Science and Technology MISiS, Russia, ²Korea University, Korea, ³Russian Academy of Science, Russia, ⁴University of Florida, USA

[MA2-4]

14:40-14:55

Size-Dependent Degradation via Sidewall Defects and Recombination Processes in InGaN-Based Micro LEDs

Jeonghyeon Park, Won Seok Cho, Jawon Kim, and Jong Kyu Kim

Pohang University of Science and Technology, Korea

[MA2-5]

14:55-15:10

Insight into Gain and Transient Response of High Gain AlGaIn/GaN UV Photodetectors: A Case Study on the Role of Incident UV Light Intensity

Wenxin Li¹, Guangyang Gu¹, Fangfang Ren^{1,2}, Dong Zhou¹, Feng Zhou¹, Weizhong Xu^{1,2}, Rong Zhang^{1,2}, Youdou Zheng¹, and Hai Lu^{1,2}

¹Nanjing University, China, ²Hefei National Laboratory, China

[MA2-6]

15:10-15:25

Analysis of GaN-Based Topological Photonic Crystal Resonator in the Visible Light Region

Takuto Honda and Akihiko Kikuchi

Sophia University, Japan

[MA2-7]

15:25-15:40

Characterization of Efficient Micro-LEDs Using Confocal Raman Spectrometer

Chuhan Deng, Zhizhong Chen, Boyan Dong, Zuojian Pan, Haodong Zhang, Ling Hu, Weihua Chen, Fei Jiao, Xiangning Kang, Qi Wang, Guoyi Zhang, and Bo Shen

Peking University, China



[MB2] Symposium GE: III-N Materials and Electronic Devices (2/7)

Session Date	Oct. 14(Mon.), 2024
Session Time	13:45-16:00
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Prof. David Zhou (Pinghu Laboratory, China) Prof. Hyun-Seop Kim (Kunsan National University, Korea)

[MB2-1] *Keynote

13:45-14:20

Wide/Ultrawide Bandgap Next Generation RF and Power Devices

Martin Kuball

University of Bristol, UK

[MB2-2] *Invited

14:20-14:45

Extending GaN Power Devices for Higher Voltages and Higher Frequencies

Jin Wei¹, Junjie Yang¹, Jiawei Cui¹, Maojun Wang¹, Xuelin Yang¹, Meng Zhang², and Bo Shen¹

¹Peking University, China, ²Beijing University of Technology, China

[MB2-3]

14:45-15:00

Recess-Free Enhancement-Mode AlGaIn/GaN RF HEMTs on Si Substrate

Tiantian Luan^{1,2}, Sen Huang^{1,2}, Guanjun Jing^{1,2}, Wenwei Zhi^{1,2}, Haibo Yin^{1,2}, Xinguo Gao^{1,2}, Ke Wei^{1,2}, Yankui Li^{1,2}, Qimeng Jiang^{1,2}, Xinhua Wang^{1,2}, Liwen Sang³, and Xinyu Liu^{1,2}

¹Institute of Microelectronics of Chinese Academy of Sciences, China, ²University of Chinese Academy of Sciences, China, ³Fudan University, China

[MB2-4]

15:00-15:15

Low RF Loss GaN HEMTs Fabrication on AlGaIn/GaN Heterostructure Grown on a Cost-Effective SAB-Bonded SiC-SiC Substrate

Guanjun Jing¹, Xinhua Wang¹, Fengwen Mu², Sen Huang¹, Qimeng Jiang¹, Ke Wei¹, and Xinyu Liu¹

¹Chinese Academy of Sciences, China, ²Innovative Semiconductor Substrate Technology Co., Ltd., China

[MB2-5]

15:15-15:30

Suppression of High Gate Leakage Current in Ohmic p-GaN Gate HEMTs

Gokhan Atmaca¹, Min-Gi Jeong², and Ho-Young Cha^{1,2}

¹ChipsK Corporation, Korea, ²Hongik University, Korea

[MB2-6]

15:30-15:45

1.48 dB-Noise Figure E-Mode Recessed-Gate GaN MOSHEMT by Neutralized Ion Beam Etching for LNA Applications

Wenbo Ye, Junmin Zhou, Haowen Guo, Han Gao, and Xinbo Zou
ShanghaiTech University, China

[MB2-7]

15:45-16:00

Single Crystal GaN Film Grown on Ceramics-AlN Substrates by MOCVD with Graphene Inter-Layer

Junkang Wu, Xuelin Yang, Zhenghao Chen, Hongcai Yang, Xingyu Fu, Faquan Wu, Haojie Wang, and Bo Shen
Peking University, China



[MC2] Symposium SiC: SiC Materials and Devices (2/4)

Session Date	Oct. 14(Mon.), 2024
Session Time	13:45-15:50
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Dr. Chunjun Liu (TanKeBlue Semiconductor Co., Ltd., China) Dr. Hyoung-Woo Kim (KERI, Korea)

[MC2-1] *Invited

13:45-14:10

Packaging Approaches for Wide Bandgap Power Semiconductors: Challenges and Efforts

Sang Won Yoon

Seoul National University, Korea

[MC2-2] *Invited

14:10-14:35

Technologies to Suppress Stacking Fault Expansion in SiC Devices: Stacking Fault Knockdown by High Energy Ion Implantation (SF-KHII) Method

Masashi Kato¹, Shunta Harada², and Hitoshi Sakane³

¹Nagoya Institute of Technology, Japan, ²Nagoya University, Japan, ³SHI-ATEX Co., Ltd., Japan

[MC2-3]

14:35-14:50

Relationship between Luminescence and Threshold Voltage Shift in SiC MOSFETs under Gate AC Stress

R. Shingo, Y. Enjoji, N. Iwaruro, and H. Yano

University of Tsukuba, Japan

[MC2-4]

14:50-15:05

Optimizing Electrical Parameters of 650V JBS Structures Using Machine Learning-Enhanced Simulation Techniques

Yan-Yu Wen, Kung-Yen Lee, Chun-Ju Chen, Pei-Chun Liao, and Xue-Fen Hu

National Taiwan University, Taiwan

[MC2-5]

15:05-15:20

Investigations on Mechanism and Suppression of Gate Voltage Oscillation for SiC Power MOSFET Switching

Zhaoxiang Wei, Guozhi Zhen, Zhaokuan Liu, Jiaying Wei, Siyang Liu, and Weifeng Sun
Southeast University, China

[MC2-6]

15:20-15:35

A Straightforward Method for Implementing the Static Characteristics of SiC MOSFETs in Spice Modeling

Y. Lee¹, S. Song¹, D. Son², S. Han², J. Lee², and H. Kang¹
¹Korea Institute of Energy Technology, Korea, ²Powermaster Semiconductor, Korea

[MC2-7]

15:35-15:50

Fabrication of Step Ring Assisted Junction Termination Extension for Edge Termination of 3.3 kV SiC PiN Diode

Sangyeob Kim¹, Hyowon Yoon², Gyuhyeok Kang¹, Sumin Park², Jinhun Kim¹, Dusan Baek², and Ogyun Seok²
¹Kumoh National Institute of Technology, Korea, ²Pusan National University, Korea



[MA3] Symposium GL: III-N Materials and Lighting Devices (3/7)

Session Date	Oct. 14(Mon.), 2024
Session Time	16:15-18:30
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Dr. Hee Jin Kim (Lumileds LLC, USA) Prof. Dong-Soo Shin (Hanyang University, Korea)

[MA3-1] *Keynote

16:15-16:50

III-Nitrides for MicroLED and Laser Devices for Display, Communication and Quantum Computing

Steven DenBaars

University of California, Santa Barbara, USA

[MA3-2] *Invited

16:50-17:15

Recent Progress of Three-Dimensional Structure-Controlled InGaN Light Emitters for Tailored Visible Spectral Control

Mitsuru Funato, Yoshinobu Matsuda, and Yoichi Kawakami

Kyoto University, Japan

[MA3-3]

17:15-17:30

Direct One-by-One Nanoscale Correlation of Real Structure and Optical Properties of a UVC/UVB-LED

Frank Bertram¹, Gordon Schmidt¹, Peter Veit¹, Jürgen Christen¹, Tai Li², Wei Luo³, and Xinqiang Wang²

¹Otto-von-Guericke-University Magdeburg, Germany, ²Peking University, China, ³Songshan Lake Materials Laboratory, China

[MA3-4]

17:30-17:45

Fabrication of High-Performance UVB LEDs and Dual-Wavelength UV LEDs

Tai Li^{1,2}, Zhaoying Chen¹, Tao Wang¹, Ye Yuan², Wei Luo², Bo Shen¹, and Xinqiang Wang^{1,2}

¹Peking University, China, ²Songshan Lake Materials Laboratory, China

[MA3-5]

17:45-18:00

Size Dependent Characteristics of DUV Micro-LEDs for High-Speed Optical Wireless Communication

Chenglong Xu, Mingyue Lou, Jichun Ye, and Wei Guo

Chinese Academy of Sciences, Ningbo, China

[MA3-6]

18:00-18:15

Inverse p-GaN Layer in Blue/Green Tandem Structure for Vertically-Stacked Full-Color Micro-LEDs

Jung-Hong Min, Sung Hoon Jung, Shang Hern Lee, Sungoh Cho, Hwa Sub Oh, and TaeHoon Chung
Korea Photonics Technology Institute, Korea

[MA3-7]

18:15-18:30

Development of MicroLED/Neural Electrode Hybrid Device

G. Shinohara¹, A. Okui¹, A. Nishikawa², A. Loesing², T. Kayama³, N. Kuga³, T. Sasaki³, and H. Sekiguchi¹
¹*Toyohashi University of Technology, Japan*, ²*ALLOS Semiconductors GmbH, Germany*, ³*Tohoku University, Japan*



[MB3] Symposium GE: III-N Materials and Electronic Devices (3/7)

Session Date	Oct. 14(Mon.), 2024
Session Time	16:15-18:30
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Dr. Feng Zhou (Nanjing University, China) Dr. Hyungseok Lee (ETRI, Korea)

[MB3-1] *Keynote

16:15-16:50

Thin-Film Diamond Integration for Enhanced Thermal Management in Electronics

Srabanti Chowdhury
Stanford University, USA

[MB3-2] *Invited

16:50-17:15

High Performance Normally-Off GaN-Based HEMTs Achieved with Recessed and Regrown Channel Structures

Joel T. Asubar¹, Shogo Maeda¹, Ali Baratov¹, Suguru Terai¹, Takahiro Igarashi¹, Kishi Sekiyama¹, Masaaki Kuzuhara², and Akio Yamamoto¹
¹University of Fukui, Japan, ²Kwansei Gakuin University, Japan

[MB3-3]

17:15-17:30

Single Crystalline AlN Heteroepitaxial Growth on Diamond (111) Substrates by Ammonia-Free High-Temperature MOCVD (AFHT-MOCVD)

X. Q. Shen, H. Kato, Y. Kato, T. Makino, and K. Kojima
National Institute of Advanced Industrial Science and Technology, Japan

[MB3-4]

17:30-17:45

Thermal Management of GaN-on-Diamond HEMTs through Electro-Thermal Modeling

Changhwan Song¹, Hyeonjin Nam¹, Jisu Kim¹, Sukwon Choi², and Jungwan Cho¹
¹Sungkyunkwan University, Korea, ²The Pennsylvania State University, USA

[MB3-5]

17:45-18:00

Toward Ultra-Thin GaN Channel on AlGaIn/GaN/AlN DH-HEMTs on AlN Substrates by Hot-Wall MOCVDMinho. Kim¹, Alexis Papamichail¹, Dat Q. Tran¹, Plamen Paskov¹, and Vanya Darakchieva^{1,2}¹Linköping University, Sweden, ²Lund University, Sweden

[MB3-6]

18:00-18:15

High Power-Performance Multiscale Vertical Scaling-down GaN-Based Heterostructure for 5G/B5G mmWave Applications

Hao Lu, Ling Yang, Bin Hou, Xiaohua Ma, and Yue Hao

Xidian University, China

[MB3-7]

18:15-18:30

AlN/GaN/AlN Quantum-Well HEMTs on Single-Crystal AlN Substrates with Silicon Delta Doping

Eungkyun Kim, Yu-Hsin Chen, Jimmy Encomendero, Debdeep Jena, and Grace Xing

Cornell University, USA



[MC3] Symposium SiC: SiC Materials and Devices (3/4)

Session Date	Oct. 14(Mon.), 2024
Session Time	16:15-18:05
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Dr. Takeshi Mitani (National Institute of Advanced Industrial Science and Technology, Japan) Dr. Youngjae Park (POSTECH, Korea)

[MC3-1] *Invited

16:15-16:40

Main Production Methods of Silicon Carbide

William Wu

ACME Inc., Taiwan

[MC3-2] *Invited

16:40-17:05

Minority Carrier Lifetime Mapping of Stacking Faults on Photoluminescence Maps from 4H-SiC Epitaxial Wafer by Time-Resolved Photoluminescence

Moonkyong Na¹, Chanhyoun Oh², Donghyun Jang², Hyundon Jung², Hyoung Woo Kim¹, Wook Bahng¹, and Soon-Ku Hong³

¹Korea Electrotechnology Research Institute, Korea, ²EtaMax Co., Ltd., Korea, ³Chungnam National University, Korea

[MC3-3]

17:05-17:20

Structures and Electronic States of Nitrogen Incorporated 4H-SiC/SiO₂ Interfaces: a First-Principles Study

Toru Akiyama¹, Hiroyuki Kageshima², and Kenji Shiraishi³

¹Mie University, Japan, ²Shimane University, Japan, ³Nagoya University, Japan

[MC3-4]

17:20-17:35

Evaluation on the Power Performance of SiC PiN Betavoltaic Cell by Using E-Beam Irradiation

Jeongtae Kim^{1,2}, Sangyeob Kim¹, Sumin Park¹, Gyuhyeok Kang¹, Ogyun Seok³, and Dong-Seok Kim²

¹Kumoh National Institute of Technology, Korea, ²Korea Atomic Energy Research Insititute, Korea, ³Pusan National University, Korea

[MC3-5]

17:35-17:50

Superior Switching Characteristics of 1.2 kV MOSFETs by Using Integration SBDs Adjacent Surface of JFET Region

Gyuhyeok Kang¹, Jinhun Kim¹, Yeongeun Park¹, Hyowon Yoon², Sangyeob Kim¹, Sumin Park², Dusan Baek², Jeongtae Kim¹, Kanghee Shin¹, and Ogyun Seok²

¹Kumoh National Institute of Technology, Korea, ²Pusan National University, Korea

[MC3-6]

17:50-18:05

Design of a 1200 V 4H-SiC P-Shield MOSFET with the Enhanced Avalanche Ruggedness under the UIS Test

Ruei-Ci Wu and Kung-Yen Lee

National Taiwan University, Taiwan

[TA1] Special Session: BN Materials and Devices (1/3)

Session Date	Oct. 15(Tue.), 2024
Session Time	10:00-12:15
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Young Duck Kim (Kyung Hee University, Korea) Prof. Soo Min Kim (Sookmyung Women's University, Korea)

[TA1-1] *Keynote
10:00-10:35
The Optical Properties of Various Polytypes of sp^2 -Bonded Boron Nitride

Bernard Gil

CNRS-Université de Montpellier, France
[TA1-2] *Invited
10:35-11:00
Recent Progress on Wafer-Scaled Monolayer Hexagonal Boron Nitride Synthesis

Ki Kang Kim

Sungkyunkwan University, Korea
[TA1-3] *Invited
11:00-11:25
Probing Deep-Ultraviolet Optoelectronic Processes in Hexagonal Boron Nitride

 Jonghwan Kim^{1,2}
¹Pohang University of Science and Technology, Korea, ²Institute for Basic Science, Korea
[TA1-4] *Invited
11:25-11:50
Current Status and Challenges in hBN Growth by Chemical Vapor Deposition

Hyeon Suk Shin

Sungkyunkwan University, Korea

[TA1-5] *Invited

11:50-12:15

Wafer-Scale AA-Stacked Hexagonal Boron Nitride Grown on GaN Substrate

Seokho Moon¹, Francis Ngome Okello Odongo¹, Adrien Rousseau², Youngjae Kim³, Yunjae Park⁴, Jiye Kim¹, Jaewon Kim⁵, Pierre Valvin², Jaehee Cho⁶, Kenji Watanabe⁷, Takashi Taniguchi⁷, Giorgia Fugallo⁸, Wilfried Desrat², Feng Ding^{4,9}, Jaedong Lee³, Bernard Gil², Guillaume Cassabois^{2,10}, Si-Young Choi¹, and Jong Kyu Kim¹

¹Pohang University of Science and Technology, Korea, ²CNRS-University of Montpellier, France, ³Daegu Gyeongbuk Institute of Science and Technology, Korea, ⁴Ulsan National Institute of Science and Technology, Korea, ⁵Samsung Advanced Institute of Technology, Korea, ⁶Jeonbuk National University, Korea, ⁷National Institute for Materials Science, Japan, ⁸University of Nantes, France, ⁹Chinese Academy of Sciences, China, ¹⁰Institut Universitaire de France, France



[TB1] Symposium GE: III-N Materials and Electronic Devices (4/7)

Session Date	Oct. 15(Tue.), 2024
Session Time	10:00-12:15
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Dr. Chih-Fang Huang (National Tsing Hua University, Taiwan) Dr. Yumin Koh (KANC, Korea)

[TB1-1] *Keynote

10:00-10:35

The Development and Progress of Monolithic GaN-Based Complementary Metal-Oxide-Semiconductor High-Electron Mobility Transistors

Ching-Ting Lee and Hsin-Ying Lee

National Cheng Kung University, Taiwan

[TB1-2] *Invited

10:35-11:00

GaN-Based p-channel Devices on High-Electron-Mobility Transistors (HEMT) Platform

Junting Chen¹, David Zhou², Zuoheng Jiang¹, Haohao Chen¹, Jinjin Tang¹, and Mengyuan Hua¹

¹*Southern University of Science and Technology, China*, ²*Shenzhen Pinghu Laboratory, China*

[TB1-3]

11:00-11:15

The Influence of Inadequate Mg Activation on Threshold Voltage Instability in p-GaN Gate HEMTs

X. Liu, C. Feng, J. Wu, D. Mao, R. Du, Z. Cai, X. Zhang, N. Gong, Y. Shi, K. Wu, C. Li, X. Wang, H. Hu, W. Zeng, D. Zhou, and Y. Wan

Shenzhen Pinghu Laboratory, China

[TB1-4]

11:15-11:30

Electrical Characteristics of p-GaN MIS Capacitors Fabricated in situ

Ren Obata, Manato Deki, Hiroataka Watanabe, Yoshio Honda, and Hiroshi Amano

Nagoya University, Japan

[TB1-5]

11:30-11:45

Advanced Nano-Characterization of Heavily Doped Pulsed Sputtered Grown GaN:Si

Gordon Schmidt¹, Frank Bertram¹, Jürgen Christen¹, Kohei Ueno², and Hiroshi Fujioka²

¹*Otto-von-Guericke-University, Germany*, ²*The University of Tokyo, Japan*

[TB1-6]

11:45-12:00

Degradation and Recovery of I-V Characteristics of n-GaN Schottky Barrier Diode due to High-Temperature Annealing and Surface Etching Process

Woong Kwon, Yuta Itoh, Seiya Kawasaki, Atsushi Tanaka, Hirotaka Watanabe, Yoshio Honda, and Hiroshi Amano

Nagoya University, Japan

[TB1-7]

12:00-12:15

Observation of Local Vibrational Modes of $\text{Mg}_{\text{Ga}}-\text{V}_{\text{N}}$ in Mg-Doped GaN

Yingming Song¹, Zidong Cai², Shixiong Zhang³, Han Yang¹, Xingyu Fu¹, Xuan Liu¹, Xuelin Yang¹, and Bo Shen¹

¹Peking University, China, ²Shenzhen Pinghu Laboratory, China, ³Hubei Normal University, China



[TC1] Symposium SiC: SiC Materials and Devices (4/4)

Session Date	Oct. 15(Tue.), 2024
Session Time	10:00-11:35
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Prof. Kung-Yen Lee (National Taiwan University, Taiwan) Prof. Ogyun Seok (Pusan National University, Korea)

[TC1-1] *Invited

10:00-10:25

New Investigations of Carrot Defects and Prismatic Stacking Faults in 4H-SiC Epitaxial Layers

Soon-Ku Hong¹, Moonkyong Na², Young Heon Kim¹, Chanhyoung Oh³, Jucheol Park⁴, Donghyun Jang³, Sung Beom Cho⁵, Hyundon Jung³, and Wook Bahng²

¹Chungnam National University, Korea, ²Korea Electrotechnology Research Institute, Korea, ³EtaMax Co., Ltd., Korea, ⁴Gumi Electronics & Information Technology Research Institute, Korea, ⁵Ajou University, Korea

[TC1-2] *Invited

10:25-10:50

Defect Characterization of Power Device Semiconductor Wafers by Novel Birefringence Method

Shunta Harada¹ and Kenta Murayama²

¹Nagoya University, Japan, ²Mipox Corporation, Japan

[TC1-3]

10:50-11:05

Experimental Study on the Influence of Induction Heating Frequency on Top-Seeded Solution Growth of 4H-SiC

Takeshi Mitani, Shigeyuki Kuboya, Kazuma Eto, and Tomohisa Kato

National Institute of Advanced Industrial Science and Technology, Japan

[TC1-4]

11:05-11:20

Hybridly Packaged White LED Composed of Fluorescent SiC and Nitride-Based near-Ultraviolet LED

T. Mizuno¹, S. Akiyoshi¹, N. Takahashi¹, T. Ban¹, M. Iwaya¹, T. Takeuchi¹, S. Kamiyama¹, A. Suzuki², E. Akazawa², Y.Ou³, J. Wang³, and H. Ou³

¹Meijo University, Japan, ²E&E Japan Co., Ltd., Japan, ³Technical University of Denmark, Denmark

[TC1-5]

11:20-11:35

High-Performance 4H-SiC Position Sensitive Detector for Ultraviolet Measurements

Yifu Wang¹, Weizong Xu^{1,2}, Dong Zhou¹, Fangfang Ren^{1,2}, Dunjun Chen¹, Rong Zhang^{1,2}, Youdou Zheng¹, and Hai Lu^{1,2}

¹Nanjing University, China, ²Hefei National Laboratory, China



[TA2] Special Session: BN Materials and Devices (2/3)

Session Date	Oct. 15(Tue.), 2024
Session Time	13:35-15:10
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Dr. Hyowon Moon (KIST, Korea) Prof. Hyeon Suk Shin (Sungkyunkwan University, Korea)

[TA2-1] *Invited

13:35-14:00

Manipulation of Carbon Color Centers in Hexagonal Boron Nitride for Efficient Deep Ultraviolet Light Emission

Young Duck Kim
Kyung Hee University, Korea

[TA2-2] *Invited

14:00-14:25

Revolutionizing Wafer-Scale Performance based on h-BN

Soo Min Kim
Sookmyung Women's University, Korea

[TA2-3]

14:25-14:40

Carbon-Related Quantum Emitters Engineering in Hexagonal Boron Nitride

Sofiya Karankova^{1,2}, Yeunjeong Lee^{1,3}, Young Gie Lee^{1,4}, Chaun Jang¹, Young Duck Kim⁴, Yong-Won Song^{1,2}, and Hyowon Moon^{1,2}

¹Korea Institute of Science and Technology, Korea, ²University of Science and Technology, Korea, ³Korea University, Korea, ⁴Kyung Hee University, Korea

[TA2-4]

14:40-14:55

Optically Active Spin Defects in Epitaxial Hexagonal Boron Nitride

K. Ludwiczak, J. Binder, A. K. Dąbrowska, P. Tatarczak, and A. Wymołek
University of Warsaw, Poland

[TA2-5]

14:55-15:10

Analog Switching Memristor based on Hexagonal Boron Nitride Grown on Gallium Nitride Substrate

Jaesub Song, Seokho Moon, Jinho Byun, Jiye Kim, Inyong Hwang, Changwook Ji, Seonghyeon Pak, and Jongkyu Kim
Pohang University of Science and Technology, Korea

[TB2] Symposium GE: III-N Materials and Electronic Devices (5/7)

Session Date	Oct. 15(Tue.), 2024
Session Time	13:35-15:10
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Prof. Joel Asubar (University of Fukui, Japan) Prof. Hyungtak Kim (Hongik University, Korea)

[TB2-1] *Invited**13:35-14:00****Advanced Fabrication Technique and Novel Device Structure for High-Performance Enhancement-Mode GaN p-MISFET**

Qi Zhou, Kuangli Chen, Liyang Zhu, Jinggui Zhou, Shuting Huang, and Bo Zhang
University of Electronic Science and Technology of China, China

[TB2-2] *Invited**14:00-14:25****Dynamic R_{on} and Buffer Trapping Mechanisms in AlGaIn/GaN HEMTs**

Hyun-Seop Kim^{1,2}, Michael J. Uren², and Martin Kuball²
¹*Kunsan National University, Korea*, ²*University of Bristol, UK*

[TB2-3]**14:25-14:40****The Impact of Carbon Impurity Ionization on the On-Resistance of GaN HEMTs**

Jinwei Zhang, Zhuoran Luo, Qianshu Wu, Miao Zhang, and Yang Liu
Sun Yat-sen University, China

[TB2-4]**14:40-14:55****Unraveling the Physical Mechanism of Current Collapse and Threshold Voltage Instability in Heterostructure-Based GaN Power Devices**

Kexin Deng^{1,2}, Sen Huang^{1,2}, Xinhua Wang^{1,2}, Qimeng Jiang^{1,2}, and Xinyu Liu^{1,2}
¹*Institute of Microelectronics of Chinese Academy of Sciences, China*, ²*University of Chinese Academy of Sciences, China*

[TB2-5]**14:55-15:10****Tuning Composition in Channel of AlGaIn HEMT Grown on AlN / SiC by MOCVD**

Joon-Hyuk Lee, Joocheol Jeong, Shyam Mohan, Jooyong Park, Jaejin Heo, and Okhyun Nam
Tech University of Korea, Korea



[TC2] Symposium GaO: Ga₂O₃ Materials and Electronic Devices (1/6)

Session Date	Oct. 15(Tue.), 2024
Session Time	13:35-15:15
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Prof. Byung Kyu Chung (Kyungpook National University, Korea) Prof. Kentaro Kaneko (Ritsumeikan University, Japan)

[TC2-1] *Keynote

13:35-14:10

Ultra-Wide Bandgap β -Ga₂O₃ and β -(Al_xGa_{1-x})₂O₃ Single Crystals and Their Physical Properties

Zbigniew Galazka

Leibniz Institute of Crystal Growth, Germany

[TC2-2] *Invited

14:10-14:35

Heteroepitaxial Growth of β -Ga₂O₃ Thin Films on Sapphire Substrates by MOCVD

Ji-Hyeon Park, Hyeong-Yun Kim, and Dae-Woo Jeon

Korea Institute of Ceramic Engineering and Technology, Korea

[TC2-3] *Invited

14:35-15:00

Unwanted Ga₂O₃ Phases in Thin Epitaxial Films and How to Prevent Them

Celesta S. Chang

Seoul National University, Korea

[TC2-4]

15:00-15:15

Phase Transition Study of Hetero-Epitaxial Ga₂O₃ Films on c-Plane Sapphire

Hyeong-Yun Kim, Ji-Hyeon Park, and Dae-Woo Jeon

Korea Institute of Ceramic Engineering and Technology, Korea

[TD1] Wide-Bandgap Semiconductor Quantum Devices 1

Session Date	Oct. 15(Tue.), 2024
Session Time	13:35-15:15
Session Room	Room D (Forum 2, 3F)
Session Chair(s)	Prof. Hosung Seo (Sungkyunkwan University, Korea) Prof. Sang-Yun Lee (GIST, Korea)

[TD1-1] *Invited**13:35-14:00****Diamond Vacancies: Engineering, Quantum Control and Applications**

Ya Wang

*University of Science and Technology of China, China***[TD1-2] *Invited****14:00-14:25****Enhancing Magnetic Field Sensitivity in a Solid-State Quantum Sensor**

Sangwon Oh

*Ajou University, Korea***[TD1-3] *Invited****14:25-14:50****Electrically Detected Photocarrier Dynamics of NV Quantum Sensor**

Hiroki Morishita

*Tohoku University, Japan***[TD1-4] *Invited****14:50-15:15****Spin-Photon Hybrid Quantum System based on Nitrogen Vacancy Venter in Diamond**

Dongyeon. D. Kang, Yong-su Lee, Ye-eun Choi, Chan-gu Kang, Eunsang Lee, Min-suk Jeon, Junghyun P. Lee, Chulk Kim, Seung-woo Jeon, and Sang-wook Han

Korea Institute for Science and Technology, Korea



[TA3] Special Session: BN Materials and Devices (3/3)

Session Date	Oct. 15(Tue.), 2024
Session Time	15:30-16:40
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Jonghwan Kim (POSTECH, Korea) Prof. Ki Kang Kim (Sungkyunkwan University, Korea)

[TA3-1] *Invited

15:30-15:55

Defect Engineering for Quantum Emissions in Hexagonal Boron Nitride

Hyowon Moon^{1,2}

¹Korea Institute of Science and Technology, Korea, ²University of Science and Technology, Korea

[TA3-2]

15:55-16:10

Uniform Growth of Hexagonal Boron Nitride on 150 mm Silicon

Muzafar Rather¹, Shao-Shiang Hsue¹, Chih-Chieh Lin¹, Yen-Huang Tien¹, Chien-Ting Wu², Kun-Lin Lin², Kun-Yu Lai¹, and Jen-Inn Chyi¹

¹National Central University, Taiwan, ²Taiwan Instrument Research Institute, National Applied Research Laboratories, Taiwan

[TA3-3]

16:10-16:25

Deep Ultraviolet Resonance Raman Spectroscopy of Hexagonal Boron Nitride

Lei Fu¹, Ning Tang¹, Yuqing Hu², Huaiyuan Yang¹, Xionghui Jia¹, Guoping Li¹, Junxi Duan², Weikun Ge¹, and Bo Shen¹

¹Peking University, China, ²Beijing Institute of Technology, China

[TA3-4]

16:25-16:40

Deterministic Creation of Tip-Induced Nanostructures in Layered Materials

Yeunjeong Lee^{1,2}, Sofiya Karankova^{1,3}, Yong Won Song^{1,3}, Su-Hyun Gong², and Hyowon Moon^{1,3}

¹Korea Institute of Science and Technology, Korea, ²Korea University, Korea, ³University of Science and Technology, Korea

[TB3] Symposium GE: III-N Materials and Electronic Devices (6/7)

Session Date	Oct. 15(Tue.), 2024
Session Time	15:30-17:00
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Prof. Sen Huang (Institute of Microelectronics of Chinese Academy of Sciences, China) Prof. Zenji Yatabe (Kumamoto University, Japan)

[TB3-1] *Keynote**15:30-16:05****Advanced GaN HEMTs Epitaxy, Terahertz Characterization and Applications**

Vanya Darakchieva^{1,2}, Alexis Papamichail², Minh Kim², Hengfang Zhang², Vallery Stanishev², Nerijus Armakavicius², Viktor Rindert¹, Mathias Schubert¹, Dat Q. Tran², Plamen Paskov², Ragnar Ferrand Drake del Castillo³, Mattias Thorsell^{3,4}, and Niklas Rorsman³

¹Lund University, Sweden, ²Linköping University, Sweden, ³Chalmers University of Technology, Sweden, ⁴SAAB AB, Sweden

[TB3-2] *Invited**16:05-16:30****Irradiation Effect and Hardened Design on Gallium Nitride Power Devices**

Feng Zhou, Can Zou, Junfan Qian, Rong Zhang, Youdou Zheng, and Hai Lu
Nanjing University, China

[TB3-3]**16:30-16:45****Heavy-Ion Irradiation-Induced Single Event Burnout Characteristic and Trap Behavior in AlGaIn/GaN MIS-HEMTs**

Can Zou, Feng Zhou, Weizong Xu, Fangfang Ren, Dong Zhou, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu
Nanjing University, China

[TB3-4]**16:45-17:00****Terahertz Optical Hall Effect in AlScN/GaN and AlYN/GaN HEMT Structures**

V. Stanishev¹, I. Streicher², A. Papamichail¹, S. Leone², and V. Darakchieva^{1,3}

¹Linköping University, Sweden, ²Fraunhofer Institute for Applied Solid State Physics IAF, Germany, ³Lund University, Sweden



[TC3] Symposium GaO: Ga₂O₃ Materials and Electronic Devices (2/6)

Session Date	Oct. 15(Tue.), 2024
Session Time	15:30-16:50
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Dr. JiHyeon Park (KICET, Korea) Dr. Zbigniew Galazka (Leibniz Institute for Crystal Growth, Germany)

[TC3-1] *Invited

15:30-15:55

Self-Assembling of Multilayered Polymorphs in Ga₂O₃

Andrej Kuznetsov
University of Oslo, Norway

[TC3-2] *Invited

15:55-16:20

Gallium Oxide Growth Study for Optoelectronic Device Applications

Gyun Seo Kim¹, Kyung-Ho Kim², Si-Young Bae⁴, Tae-Yong Park³, Boon S. Ooi³, and Jungwook Min^{1,3}
¹*Kumoh National Institute of Technology, Korea*, ²*Korea Institute of Ceramic Engineering and Technology, Korea*, ³*King Abdullah University of Science and Technology, Saudi Arabia*, ⁴*Pukyong National University, Korea*

[TC3-3]

16:20-16:35

Thermal Conductivity Measurements of MOCVD-Grown Ga₂O₃ Heterostructures

Taeyeon Kim¹, Hyeonyun Kim², Hongju Mun¹, Jihyeon Park², Jihyeon Kim¹, Daewoo Jeon², and Jungwan Cho¹
¹*Sungkyunkwan University, Korea*, ²*Korea Institute of Ceramic Engineering and Technology, Korea*

[TC3-4]

16:35-16:50

Point and Extended Defects, and Their Pathway to Phase Transformation of Gallium Oxide

Chris Chae, Hsien-lien Huang, and Jinwoo Hwang
The Ohio State University, USA

[TD2] Wide-Bandgap Semiconductor Quantum Devices 2

Session Date	Oct. 15(Tue.), 2024
Session Time	15:30-16:35
Session Room	Room D (Forum 2, 3F)
Session Chair(s)	Prof. Sang-Yun Lee (GIST, Korea) Prof. Sangwon Oh (Ajou University, Korea)

[TD2-1] *Invited**15:30-15:55****Quantum Sensing based on Silicon Vacancy in SiC toward Diagnosis Tool for SiC Power Devices**Takeshi Ohshima^{1,2}, Tomoaki Tanaka¹, and Yuichi Yamazaki¹¹National Institutes for Quantum Science and Technology, Japan, ²Tohoku University, Japan**[TD2-2] *Invited****15:55-16:20****The Impact of Paramagnetic Defects on the Performance of Quantum Devices in Diamond**

Hosung Seo

Sungkyunkwan University, Korea

[TD2-3]**16:20-16:35****High-Q SiC Photonic Nanocavities near Optical Transition of Color Centers**Heungjoon Kim¹, Bong-Shik Song², Takashi Asano¹, and Susumu Noda¹¹Kyoto University, Japan, ²Sungkyunkwan University, Korea



[TA4] Symposium GL: III-N Materials and Lighting Devices (4/7)

Session Date	Oct. 15(Tue.), 2024
Session Time	17:00-18:10
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Young Joon Hong (Sungkyunkwan University, Korea) Prof. Lai Wang (Tsinghua University, China)

[TA4-1] *Invited

17:00-17:25

Progress and Challenges in GaN Based High Efficiency RGB Micro-LEDs for Comprehensive Applications

Bin Liu¹, Feifan Xu¹, Yimeng Sang¹, Tao Tao¹, Zhe Zhuang¹, Jinchai Li², Kai Huang², and Rong Zhang²

¹Nanjing University, China, ²Xiamen University, China

[TA4-2]

17:25-17:40

Vertical-Emitting InGaN Tunnel-Junction Nanorod Photonic Crystal Lasing Device

Sung-Un Kim, Min-Seok Lee, Dae-Young Um, Jeong-Kyun Oh, Vignesh Veeramuthu, and Yong-Ho Ra

Jeonbuk National University, Korea

[TA4-3]

17:40-17:55

Enhancement of Single-Photon Emission Brightness of Position-Controlled GaN Defects in Telecom Range Using Patterned Sapphire Substrates

Hyemin Kim^{1,2}, Yong-Ho Song¹, Young-Ho Ko², and Yong-Hoon Cho¹

¹Korea Advanced Institute of Science and Technology, Korea, ²Electronics and Telecommunications Research Institute, Korea

[TA4-4]

17:55-18:10

Study on AlN Surface Oxidation for Polarity-Inverted Stacking Structures

Tomohiro Tamano¹, Kanako Shojiki^{1,2}, Ryota Akaike¹, Hiroki Yasunaga¹, Takao Nakamura¹, Masahiro Uemukai³, Tomoyuki Tanikawa³, Ryuji Katayama³, and Hideto Miyake¹

¹Mie University, Japan, ²Kyoto University, Japan, ³Osaka University, Japan

[TB4] Symposium GE: III-N Materials and Electronic Devices (7/7)

Session Date	Oct. 15(Tue.), 2024
Session Time	17:00-18:35
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Dr. Gokhan Atmaca (ChipsK Corporation, Korea) Prof. Jeong-Gil Kim (Dong-A University, Korea)

[TB4-1] *Invited

17:00-17:25

GaN and Wide-Bandgap Semiconductor Devices for Power Electronics Applications

J.Buckley¹, P.Godignon¹, C.Le Royer¹, E.Nowak¹, R.Escoffier¹, M.El Amrani^{1,4}, V. Ackermann¹, M.Charles¹, H.El Rammouz¹, B.Mohamad¹, T.Labau^{1,2}, C.Masante¹, C. Piotrowicz^{1,3}, J.Zgheib¹, M.Kumar¹, M.Fayolle¹, J.Biscarrat¹, S.Bécu¹, T.Kaltsounis^{1,6}, Z. M Qaddem¹, D.Plaza Arguello¹, S.Torrenço¹, M.Gorisse¹, V.Maurya^{1,4}, C.Gillot¹, and Y.Lamy¹

¹Grenoble Alpes University, France, ²Delphea, France, ³University of Bordeaux, France, ⁴University of Tours, France, ⁵Côte d'Azur University, France

[TB4-2] *Invited

17:25-17:50

Recent Progress of GaN Power Intergation and Modeling Technology

Sheng Li, Siyang Liu, Yanfeng Ma, Mingfei Li, Weihao Lu, and Weifeng Sun
Southeast University, China

[TB4-3]

17:50-18:05

Ion Beam Etching Enabled Recessed-Gate E-mode GaN MOS-HEMT with FOM of 701 MW-cm⁻² and Monolithic Integrated Digital Circuit

Han Gao, Yitian Gu, Yitai Zhu, Wenbo Ye, and Xinbo Zou
ShanghaiTech University, China

[TB4-4]

18:05-18:20

X-Ray Irradiation-Induced Threshold Voltage Instability in Schottky-Gate P-GaN HEMTs

Yu Rong, Feng Zhou, Weizong Xu, Fangfang Ren, Dong Zhou, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu
Nanjing University, China



[TB4-5]

18:20-18:35

Surface Morphologies and Electrical Properties of N-type GaN Films Deposited by Two Different Sputtering Methods

S. Yamada, K. Tanaka, M. Arai, T. Kachi, and J. Suda
Nagoya University, Japan

[TC4] Symposium GaO: Ga₂O₃ Materials and Electronic Devices (3/6)

Session Date	Oct. 15(Tue.), 2024
Session Time	17:00-17:50
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Dr. Dae-Woo Jeon (KICET, Korea) Prof. Andrej Kuznetsov (University of Oslo, Norway)

[TC4-1] *Invited**17:00-17:25****Machine-Learning Dynamic Model of Complex Ga₂O₃ Polymorphs for Next-Generation Extreme Environment Electronics**

Junlei Zhao¹, Mengyuan Hua¹, Jesper Byggmästar², Jiahui Zhang², Kai Nordlund², Flyura Djurabekova², Javier García-Fernández³, Alexander Azarov³, and Andrej Kuznetsov³

¹*Southern University of Science and Technology, China*, ²*University of Helsinki, Finland*, ³*University of Oslo, Norway*

[TC4-2] *Invited**17:25-17:50****Potential of Germanium Dioxide (GeO₂) for Power Devices**

Kentaro Kaneko

Ritsumeikan University, Japan



[TD3] Novel Devices

Session Date	Oct. 15(Tue.), 2024
Session Time	17:00-17:45
Session Room	Room D (Forum 2, 3F)
Session Chair(s)	Prof. Dong-Seon Lee (GIST, Korea) Prof. Dong-Soo Shin (Hanyang University, Korea)

[TD3-1]

17:00-17:15

Analysis of Emission Properties of Metal–Semiconductor Micro–Stripe Structures with Respect to the Materials

Daiki Yoshikawa¹, Bojin Lin¹, Hnin Lai Lai Aye¹, Kohei Ueno², Hiroshi Fujioka², Hideto Miyake³, and Yoshihiro Ishitani¹

¹Chiba University, Japan, ²The University of Tokyo, Japan, ³Mie University, Japan

[TD3-2]

17:15-17:30

Thermal Conductivity Measurements of BeO Thin Films Grown by Plasma Enhanced Atomic Layer Deposition

Jihyun Kim¹, Jonghyun Bae², Dongyun Seo¹, Dohwan Jung², Jungwoo Oh², and Jungwan Cho¹

¹Sungkyunkwan University, Korea, ²Yonsei University, Korea

[TD3-3]

17:30-17:45

PEC Water Splitting based on III-Nitride Nanorods for Enhancing Hydrogen Production

Jeong-Kyun Oh, Dae-Young Um, Bagavath Chandran, Sang-Wook Lee, Sung-Un Kim, Cheul-Ro Lee, and Yong-Ho Ra

Jeonbuk National University, Korea

[WA1] Symposium GL: III-N Materials and Lighting Devices (5/7)

Session Date	Oct. 16(Wed.), 2024
Session Time	09:00-10:50
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Takao Oto (Yamagata University, Japan) Prof. Hideto Miyake (Mie University, Japan)

[WA1-1] *Invited

09:00-09:25

Controlling the Growth Mode of Graphene Assisted Growth via Graphene Defects

Jeongwoon Kim¹, Hyeon Woo Kim^{2,3}, Jongil Kim⁴, Je-Sung Lee¹, Hoe-Min Kwak⁵, Jaeyoung Baik¹, Soo-Young Choi¹, Jinsoo Kim¹, Si-Young Bae⁸, Sung Beom Cho⁶, Sangho Oh⁴, Young-Joon Hong⁷, and Dong-Seon Lee¹
¹Gwangju Institute of Science and Technology, Korea, ²Hanyang University, Korea, ³Korea Institute of Ceramic Engineering and Technology, Korea, ⁴Korea Institute of Energy Technology, Korea, ⁵Electronics and Telecommunications Research Institute, Korea, ⁶Ajou University, Korea, ⁷Sungkyunkwan University, Korea, ⁸Pukyong National University, Korea

[WA1-2] *Invited

09:25-09:50

Atomic Evolution Mechanism and Suppression of Edge Threading Dislocations in Remote Epitaxy

Chen Qi and Liu zhiqiang
 Chinese Academy of Sciences, China

[WA1-3]

09:50-10:05

Van der Waals Epitaxial High-Quality Wide Bandgap Nitride Thin Film Materials and High-Performance Devices

Haidi Wu, Jing Ning, Jincheng Zhang, and Yue Hao
 Xidian University, China

[WA1-4]

10:05-10:20

Remote Homoepitaxy of Gr/N-polar GaN for Exfoliation and Deformable Device

Joonghoon Choi and Young Joon Hong
 Sungkyunkwan University, Korea



[WA1-5]

10:20-10:35

Quasi-Van Der Waals Epitaxial Growth of InGaN Quantum Wells on Transferred and As-Grown H-BN via Metal Organic Vapor Phase Epitaxy

Peilong Yang¹, Seokho Moon², Zhibiao Hao¹, Yi Luo¹, Changzheng Sun¹, Bing Xiong¹, Yanjun Han¹, Jian Wang¹, Hongtao Li¹, Lin Gan¹, Jong Kyu Kim², and Lai Wang¹

¹Tsinghua University, China, ²Pohang University of Science and Technology, Korea

[WA1-6]

10:35-10:50

AlN with Carbon Buffer for Epitaxial Lift-off of III-Nitride Devices

Hae-Gon Oh, Young-Jun Choi, and Hae-Yong Lee

LumiGNtech Co., Ltd., Korea

[WB1] Symposium GaO: Ga₂O₃ Materials and Electronic Devices (4/6)

Session Date	Oct. 16(Wed.), 2024
Session Time	09:00-10:40
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Prof. Youseung Lim (Sejong University, Korea) Prof. Flyura Djurabekova (University of Helsinki, Finland)

[WB1-1] *Keynote

09:00-09:35

Demand and Technology Development Trends for Vehicle Power Semiconductors

Youngkyun Jung

*Hyundai Motor Company, Korea***[WB1-2] *Invited**

09:35-10:00

Recent Efforts for Commercial Applications of Ga₂O₃ Devices

Shizuo Fujita

*Kyoto University, Japan***[WB1-3] *Invited**

10:00-10:25

Beta-Gallium Oxide Nanowire-Based Electronic DevicesMinglei Tang^{1,2}, Siyuan Xu^{1,3}, Guangming Qu^{1,2}, Lining Liu^{1,3}, Guodong Wang², Young Jin Lee⁴, Dae-Woo Jeon⁴, Ji-Hyeon Park⁴, Yiyun Zhang^{1,3}, Xiaoyan Yi^{1,3}, Junxi Wang^{1,3}, and Jinmin Li^{1,2}¹Chinese Academy of Sciences, China, ²Henan Polytechnic University, China, ³University of Chinese Academy of Sciences, China, ⁴Korea Institute of Ceramic Engineering and Technology, Korea**[WB1-4]**

10:25-10:40

pn Heterojunction Made of Ga₂O₃ and NiO Using RF-SputteringHeejeong Ryou¹, Sunjae Kim¹, Minje Kim¹, Dong-Bin Kim², Jongsu Baek², Byung Jin Cho², and Wan Sik Hwang¹¹Korea Aerospace University, Korea, ²Korea Advanced Institute of Science and Technology, Korea



[WC1] Special Session: Diamond Materials and Devices (1/3)

Session Date	Oct. 16(Wed.), 2024
Session Time	09:00-10:40
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Prof. Okhyun Nam (Tech University of Korea, Korea) Dr. Tokuyuki Teraji (National Institute for Materials Science, Japan)

[WC1-1] *Keynote

09:00-09:35

Diamond RF Planar and Power Vertical p-FET Using 2D Hole Gas

H. Kawarada¹, K. Ota^{1,2}, K. Kudara¹, N. Oji², and T. Fujishima²

¹Waseda University, Japan, ²Power Diamond Systems, Inc., Japan

[WC1-2] *Invited

09:35-10:00

Two-Inch High Quality Diamond Heteroepitaxial Growth on Sapphire Substrate

Seong-Woo Kim

Orbray Co., Ltd., Japan

[WC1-3] *Invited

10:00-10:25

Diamond Growth on the Heteroepitaxial Diamond Substrate for Future Power and Quantum Device Applications

Taemyung Kwak¹, Geunho Yoo¹, Uiho Choi¹, Seong-Woo Kim², and Okhyun Nam¹

¹Tech University of Korea, Korea, ²Orbray Co., Ltd., Japan

[WC1-4]

10:25-10:40

Coupling X-Ray Beam Induced Current and X-Ray Diffraction Imaging to Characterize Diamond Plates Used as Semiconductor-Based Detectors

F. Lafont¹, M.L. Gallin-Martel², D. Dauvergne², P. Everaere^{1,2}, R. Molle², J. Baruchel¹, and T.N. Tran Caliste¹

¹The European Synchrotron Radiation Facility, France, ²Laboratoire de Physique Subatomique & Cosmologie, France

[WA2] Symposium GL: III-N Materials and Lighting Devices (6/7)

Session Date	Oct. 16(Wed.), 2024
Session Time	11:00-11:55
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Dr. Julien Brault (Cote Azur University - CNRS - CRHEA, France) Prof. Zhiqiang Liu (Chinese Academy of Sciences, China)

[WA2-1] *Invited

11:00-11:25

Efficiency Increase in 220-230 nm Far-UVC LEDs and 200 mW Class 230 nm Power LED Module Grown on c-Sapphire

Hideki Hirayama¹, M. Ajmal Khan¹, Mitsuhiro Muta², Yukio Kashima¹, Eriko Matsuura¹, and Yasushi Iwaisako²
¹RIKEN, Japan, ²Nippon Tungsten Co., Ltd., Japan

[WA2-2]

11:25-11:40

Development of Vertical AlGaIn-Based UV-B Laser Diode Using Substrate Exfoliation Technology by Heated-Pressurized Water

Motoaki Iwaya¹, Yusuke Sasaki¹, Yoshinori Imoto¹, Ryoya Yamada¹, Takumu Saito¹, Rintaro Miyake¹, Shundai Maruyama¹, Shogo Karino¹, Sho Iwayama¹, Satoshi Kamiyama¹, Tetsuya Takeuchi¹, and Hideto Miyake²
¹Meijo University, Japan, ²Mie University, Japan

[WA2-3]

11:40-11:55

Study of Strain-Induced Quantum Wells Shallowing in 230 nm UVC LEDs and Their Influence on Hole Overflow

Ping-Jie Zhuang and Yuh-Renn Wu
 National Taiwan University, Taiwan



[WB2] Symposium GaO: Ga₂O₃ Materials and Electronic Devices (5/6)

Session Date	Oct. 16(Wed.), 2024
Session Time	11:00-12:20
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Dr. Sin Su Kyoung (PowerCubeSemi Co., Ltd., Korea) Prof. Shizuo Fujita (Kyoto University, Japan)

[WB2-1] *Invited

11:00-11:25

Atom-Level Mechanisms of Exceptional Radiation Tolerance of Gallium Oxide

Ru He¹, Huan He^{1,2}, Junlei Zhao³, Huan Liu¹, Ilja Makkonen¹, and Flyura Djurabekova¹

¹University of Helsinki, Finland, ²Xi'an Jiaotong University, China, ³Southern University of Science and Technology, China

[WB2-2] *Invited

11:25-11:50

Putting the Pieces Together for Gallium Oxide Power Devices

M. H. Wong, W. Zhou, Z. Wen, J. Yang, S. Huang, H. Zhou, and Z. Li

Hong Kong University of Science and Technology, Hong Kong S.A.R

[WB2-3]

11:50-12:05

High-Performance Self-Powered UV Photodetector based on p-CuAlO₂/β-Ga₂O₃ Heterojunction

Chowdam Venkata Prasad and You Seung Rim

Sejong University, Korea

[WB2-4]

12:05-12:20

Deep Traps and Electrical Properties of NiO-Ga₂O₃ Heterojunction Diodes Versus Ni Schottky Diodes and Effects of Proton Irradiation

Anastasiia I. Kochkova¹, Alexander Y. Polyakov¹, Eugene B. Yakimov^{1,2}, Danila S. Saranin¹, Alexey V. Chernykh¹, Anton A. Vasilev¹, Pavel A. Gostishchev¹, Luiza A. Alexanyan¹, Nikolai R. Matros¹, Ivan V. Shchemerov¹, Petr B. Lagov^{1,3}, and Stephen J. Pearton⁴

¹The National University of Science and Technology MISiS, Russia, ²Institute of Microelectronics Technology and High Purity Materials, Russia, ³Laboratory of Radiation Technology, Russia, ⁴University of Florida, USA

[WC2] Special Session: Diamond Materials and Devices (2/3)

Session Date	Oct. 16(Wed.), 2024
Session Time	11:00-12:20
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Prof. Hiroshi Kawarada (Waseda University, Japan) Dr. Seong-Woo Kim (Orbray Co., Ltd., Japan)

[WC2-1] *Invited

11:00-11:25

Recent Progress in Diamond Semiconductors

Hong-Xing Wang

*Xi'an Jiaotong University, China***[WC2-2] *Invited**

11:25-11:50

Recent Advances in Diamond MOSFET Technologies

Norio Tokuda¹, Tsubasa Matsumoto¹, Xufang Zhang¹, Kai Sato¹, Kazuki Kobayashi¹, Kimiyoshi Ichikawa¹, Kan Hayashi¹, Takao Inokuma¹, Satoshi Yamasaki¹, Christoph E. Nebel^{1,2}, Hiromitsu Kato³, Masahiko Ogura³, Toshiharu Makino³, and Daisuke Takeuchi³

¹Kanazawa University, Japan, ²Diamond and Carbon Applications, Germany, ³National Institute of Advanced Industrial Science and Technology, Japan

[WC2-3]

11:50-12:05

Experimental Measurement of Carrier Velocity in Surface-Transfer-Doped Diamond PFETs

Wesley Turner and Patrick Fay

*University of Notre Dame, USA***[WC2-4]**

12:05-12:20

Hydrogen-Terminated Diamond MOSFET Fabricated on Heteroepitaxial Grown Diamond

Taemyung Kwak, Yeonghwa Kwon, Seolyoung Oh, Yoonseok Nam, Geunho Yoo, and Okhyun Nam

Tech University of Korea, Korea



[WA3] Symposium GL: III-N Materials and Lighting Devices (7/7)

Session Date	Oct. 16(Wed.), 2024
Session Time	13:40-17:00
Session Room	Room A (Monterosso, B1F)
Session Chair(s)	Prof. Young Joon Hong (Sungkyunkwan University, Korea) Dr. Jung-Hong Min (KOPTI, Korea) Dr. Jong Hyeob Baek (KOPTI, Korea)

[WA3-1] *Keynote

13:40-14:15

ZOGAN LED: Breakthrough for MicroLED Displays

Y. R. Ryu^{1,2}, Sung K. Hong¹, Moon W. Bang¹, Sung-Ran Jeon², Ja Yeon Kim², Jong-Hyeop Baek², Dong-Min Jeon³, Dong-Soo Shin³, and Jong-In Shim³

¹ZOGAN SEMI, Korea, ²Korea Photonics Technology Institute, Korea, ³Hanyang University, Korea

[WA3-2] *Invited

14:15-14:40

Investigation of AlGaN Heterostructures Grown on h-BN by Molecular Beam Epitaxy for the Fabrication of Deep UV LEDs

J. Brault¹, S. Mitra¹, S. Shetty¹, S. Chenot¹, M. Nemoz¹, A. Zaiter¹, M. Al Khalfioui¹, P. Vuong²,

V. Ottapilakkal², S. Sundaram², A. Ibanez³, P. Valvin³, G. Cassabois³, B. Gil³, and A. Ougazzaden^{2,4}

¹CNRS-CRHEA-Cote Azur University, France, ²Georgia Tech Europe, France, ³University of Montpellier, France, ⁴Georgia Institute of Technology, USA

[WA3-3]

14:40-14:55

Low Temperature Growth of GaN Films with Ion Beam Assisted Magnetron Sputtering

Yongjun Park, Changmin Yun, Seung Yup Baek, Gyulim Kim, Yosep Choi, and In-Hwan Lee
Korea University, Korea

[WA3-4] *Invited

15:00-15:25

Deep-UV LEDs Fabricated on Face-to-Face Annealed Sputter-Deposited AlN Templates

Hideito Miyake, Ryota Akaike, Hiroki Yasunaga, and Takao Nakamura
Mie University, Japan

[WA3-5] *Invited

15:25-15:50

Improvement of Emission Efficiency and Optical Functionality for Visible Light Region by Designing InGaN-Based Periodic NanostructuresTakao Oto¹, Koichi Okamoto², Rie Togashi³, Akihiko Kikuchi³, and Katsumi Kishino³¹Yamagata University, Japan, ²Osaka Metropolitan University, Japan, ³Sophia University, Japan

[WA3-6]

15:50-16:05

Reduction of Forward Voltage in 230 nm AlGaIn far-UVC LED Using Polarization Assisted AlGaIn Hole Injection LayerFujimoto Kohei^{1,2}, Mitsuhiro Muta³, M. Ajmal Khan¹, Sachie Fujikawa^{1,2}, Hiroyuki Yaguchi², Yasushi Iwaisako³, and Hideki Hirayama¹¹RIKEN, Japan, ²Saitama University, Japan, ³Nippon Tungsten Co., Ltd., Japan

[WA3-7] *Invited

16:10-16:35

Development of UVC LEDs Ranging from 230nm to 275nm

Myeong Seok Oh, Hae Jin Park, Tae Wan Kwon, and Seung Kyu Oh

PhotonWave Co., Ltd., Korea

[WA3-8]

16:35-17:00

Highly Conductive Al-rich n-AlGaIn for Deep-Ultraviolet Light Emitters

Jiaming Wang, Fujun Xu, Lisheng Zhang, Jing Lang, Chen Ji, Chengzhi Ji, Xiangning Kang, Zhixin Qin, Weikun Ge, and Bo Shen

Peking University, China



[WB3] Symposium GaO: Ga₂O₃ Materials and Electronic Devices (6/6)

Session Date	Oct. 16(Wed.), 2024
Session Time	13:40-15:05
Session Room	Room B (Vernazza, 3F)
Session Chair(s)	Prof. Wan Sik Hwang (Korea Aerospace University, Korea)

[WB3-1] *Invited

13:40-14:05

Temperature-Controlled Growth of β -Ga₂O₃ Single Crystals by Edge-Defined Film-Fed Growth Method

Si-Young Bae¹, Woon-Hyeon Jeong², A-Ran Shin^{2,3}, Tae-Hun Gu^{2,3}, Yun-Ji Shin², and Seong-Min Jeong³

¹Pukyong National University, Korea, ²Korea Institute of Ceramic Engineering and Technology, Korea, ³Pusan National University, Korea

[WB3-2]

14:05-14:20

Observation of Temperature-Dependent Capture Cross-Section for Main Deep-Levels in β -Ga₂O₃

Anton A. Vasilev¹, Anastasiia I. Kochkova¹, Alexander Y. Polyakov¹, Andrei A. Romanov¹, Nikolai R. Matros¹, Luiza A. Alexanyan¹, Ivan V. Shchemerov¹, and Stephen J. Pearton²

¹National University of Science and Technology MISIS, Russia, ²University of Florida, USA

[WB3-3]

14:20-14:35

Temperature-Dependent Electrical and Trap Properties of β -Ga₂O₃ Schottky Barrier Diodes w/o Homoepitaxial Layer

Jiaxiang Chen^{1,2}, Haolan Qu², Haitao Du², Xing Lu³, Yuxi Wan¹, Daohua Zhang¹, and Xinbo Zou²

¹Shenzhen Pinghu Laboratory, China, ²ShanghaiTech University, China, ³Sun Yat-sen University, China

[WB3-4]

14:35-14:50

Normally-off β -Ga₂O₃ DUV Phototransistor Grown by MOCVD

Sunjae Kim^{1,2}, Dae-Woo Jeon¹, Wan Sik Hwang², and Ji-Hyeon Park¹

¹Korea Institute of Ceramic Engineering and Technology, Korea, ²Korea Aerospace University, Korea

[WB3-5]

14:50-15:05

Investigation The Characteristics of α -Ga₂O₃ Photodetector upon Soft X-Ray Irradiation

Huong T. T. Vo¹, Sunjae Kim^{1,2}, Minje Kim¹, Hyeon Gu Cho³, Se Hoon Gihm³, Ji-Hyeon Park², Dae-Woo Jeon², and Wan Sik Hwang¹

¹Korea Aerospace University, Korea, ²Korea Institute of Ceramic Engineering and Technology, Korea,

³AweXome Ray Inc., Korea

[WC3] Special Session: Diamond Materials and Devices (3/3)

Session Date	Oct. 16(Wed.), 2024
Session Time	13:40-15:00
Session Room	Room C (Forum 1, 3F)
Session Chair(s)	Prof. Hong-Xing Wang (Xi'an Jiaotong University, China) Prof. Geunho Yoo (Tech University of Korea, Korea)

[WC3-1] *Invited**13:40-14:05****Diamond Growth by Chemical Vapor Deposition for Quantum Device Applications**

Tokuyuki Teraji

*National Institute for Materials Science, Japan***[WC3-2] *Invited****14:05-14:30****Status of CVD Diamond Growth and Engineering for High-End Applications**Jocelyn Achard¹, Alexandre Tallaire^{1,2}, Ovidiu Brinza¹, Riadh Issaoui¹, Lahcene Mehmel¹, Vianney Mille¹, and Fabien Bénédic¹¹University Sorbonne Paris Nord, France, ²PSL Research University, France**[WC3-3]****14:30-14:45****Thermal Conductivity Modeling of Sub-1 μm Polycrystalline Diamond Thin Films**Jongwon Baek¹, Junyoung Bae¹, Takuma Hori², and Jungwan Cho¹¹Sungkyunkwan University, Korea, ²Tokyo University of Agriculture and Technology, Japan**[WC3-4]****14:45-15:00****Imaging the Stress Tensor near Dislocation in Diamond Using Solid State Quantum Sensor**

Takeyuki Tsuji and Tokuyuki Teraji

National Institute for Materials Science, Japan